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THIS MESSAGE I	has34pages includ	DING THIS SHEET	
TO:	Assistant Commission	ner for Patents	
FAX NO.:	703-872-9310		
FROM:	Keith Taboada, Esq.		
DATE:	February 7, 2002		+
MATTER:	Serial No. 09/519.719	Filed: March 7, 2000 C	AC.
DOCKET NO.:	4150	~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~	2014
APPLICANT:	Noorbakhsh, et al.	0,	
The following has been	received in the U.S. Patent an	d Trademark Office on the date of this facsimile	<u> </u>
Petition Disclosure Statement & PTO-1449 X Drawings (4 sheets) red-lined X Drawings (4 sheets) formal X Amendment (21 pages) w/Petition for Extension of Time		X Transmittal Letter (2 copies) X Fee Transmittal (2 copies) X Deposit Account Transaction X Facsimile Transmission Certificate dated February 7, 2002	CA
I hereby certif	y that this correspondence is buts, Washington, DC 20231 or	eing transmitted by facsimile to the Assistant February 7, 2002	
Allyson M. De Name of person signing	eVesty z this certificate	Allyson M. Selesty 27-02 Signature and date	

Commissioner for Patents, Washington, DC 20231 (Facsimile No. (703) 872-9310	on February 7, 200	02
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HERIDAN	

Please type a plus sign (+) inside this box	→ [±]	Approved U.S. Patent and Trademark (guited to respond to a collection of inform	PTO/SB/21 (08-00) for use through 10/31/2002. OMB 0651-0031 Office: U.S. DEPARTMENT OF COMMERCE office: U.S. DEPARTMENT OF COMMERCE auton unless it displays a valid OMB control number. 09/519,719
Under the Paperwork Reduction Act of 1995, no pa	1	Application Number	09/519,719
TRANSMITTAL FORM (to be used for all correspondence after initial filling)		Filing Date	March 7, 2000
		First Named Inventor	Noorbakhsh, et al.
		Group Art Unit	1763
		Examiner Name	Alejandro Mulero
a halon		Attorney Docket Number	4150
Total Number of Pages in This Submission		OSURES (check all that apply)	
Fee Transmittal Form Fee Attached Amendment / Response After Final Affidavits/declaration(s) Extension of Time Request Express Abandonment Request Information Disclosure Statement Certified Copy of Priority Document(s)	Assign (for ar International I	nment Papers 1 Application)	After Allowance Communication to Group Appeal Communication to Board of Appeals and Interferences Appeal Communication to Group (Appeal Notice, Briat, Reply Brief) Proprietary Information Status Letter Other Enclosure(s) (please identity below): Four (4) red-lined drawings Four (4) sheets of formal drawings
Response to Missing Parts/ Incomplete Application Response to Missing Parts under 37 CFR 1,52 or 1.53 SIGN Firm or Individual name Signature	Een	e OF APPLICANT, ATTORNE	Y, OR AGENT
Date February 7, 200	2		



AMENDMENT: Page 1 of 21 S/N 09/519,719 4150/ETCH/DRIE/JB1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

Applicant: Noorbakhsh, et al.

Case: 4150

Serial No.: 09/519,719

Filed: March 7, 2000

Examiner: Alejandro Mulero

Group Art Unit: 1763

Title:

TEMPERATURE CONTROLLED SEMICONDUCTOR PROCESSING

CHAMBER LINER

ASSISTANT COMMISSIONER FOR PATENTS Washington, DC 20231

SIR:

<u>AMENDMENT</u>

In response to the Office Action dated October 11, 2001, 2001 (Paper No.

4), please amend the above-identified patent application as follows: Or CROUD TOUR

IN THE CLAIMS

Please replace the indicated claims as follows:

11. (AMENDED) A semiconductor processing chamber comprisi

a wall, a bottom and a lid assembly defining a chamber volume;

a substrate support disposed within the chamber volume; and

a chamber liner disposed in the chamber volume and circumscribing the substrate support, the chamber liner having a passage at least partially disposed in the chamber line, the passage fluidly isolated from the chamber volume and having an inlet and outlet adapted to flow a fluid through the passage.